TSMC-98-420



March 18, 2002

To: Commissioner of Patents and Trademarks

Washington, D.C. 20231

Fr: George O. Saile, Reg. No. 19,572

20 McIntosh Drive

Poughkeepsie, N.Y. 12603

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HAR 29 2002
TECHNOLUGY VEHICER 2

Subject:

Serial No. 10/037,586 01/04/02

Hsueh-Heng Liu

A METHOD TO PREVENT ANTIFUSE Si DAMAGE USING SIDEWALL SPACERS

Grp. Art Unit:

INFORMATION DISCLOSURE STATEMENT

Enclosed is Form PTO-1449, Information Disclosure Citation In An Application.

The following Patents and/or Publications are submitted to comply with the duty of disclosure under CFR 1.97-1.99 and 37 CFR 1.56. Copies of each document is included herewith.

CERTIFICATE OF MAILING

I hereby certify that this correspondence is being deposited with the United States Postal Service as first class mail in an envelope addressed to: Commissioner of Patents and Trademarks, Washington, D.C. 20231, on March 22, 2002.

Stephen B. Ackerman, Reg.# 37761

Signature/Date

3/22/02

TSMC-98-420

- U.S. Patent 5,508,220 to Eltoukhy et al., "Method of Forming Antifuses Having Minimum Areas," discloses a method to form anitfuses.
- U.S. Patent 5,763,299 to McCollum et al., "Reduced Leakage Antifuse Fabrication Method," discloses a method to reduce leakage for antifuses.
- U.S. 5,807,786 to Chang, "Method of Making a Barrier Layer to Protect Programmable Antifuse Structure from Damage During Fabrication Sequence," discloses a barrier layer to protect an antifuse.

Sincerely,

Stephen B. Ackerman,

Reg. No. 37761

